

	Hits	Search Text	DBs
36	4	((mask or photomask or reticle) same (phase near6 shift\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((dual near9 layer) or (double near9 layer) or ((upper or top) near29 (bottom or lower))) or (first near22 second)) near26 (resist or photoresist or photosensitive) near29 (substrate or wafer))) and ((partial\$4 near9 transmit\$4) same (mask or reticle or photomask)) and ((photoresist or resist) same (plurality or different) same develop\$4 same thickness)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
37	1	((mask or photomask or reticle) same (phase near6 shift\$4) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((dual near9 layer) or (double near9 layer) or ((upper or top) near29 (bottom or lower))) or (first near22 second)) near26 (resist or photoresist or photosensitive) near29 (substrate or wafer))) and ((partial\$4 near9 transmit\$4) same (mask or reticle or photomask)) and ((variable or different or varying or differing) near22 sensitiv\$6 near26 (resist or photoresist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
38	3	((mask or photomask or reticle) same ((alternat\$4 near12 phase near9 shift\$4) or (phase near6 shift\$4) or (half near9 tone)) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((dual near9 layer) or (double near9 layer) or ((upper or top or first) near22 (bottom or lower or second)) or (first near12 second)) near20 (resist or photoresist or photosensitive) near9 (substrate or wafer))) and (partial\$4 near9 transmit\$4) and ((photoresist or resist) same (pluralit\$4 or different) same thickness\$2)	US-PGPUB